ASD2023 featuring Special Session of ALD for Semiconductors

April 2-5, 2023, Incheon National University, Incheon, Korea



Call for Papers (Jan 16 - Feb 6) http://asd2023.com

- Mechanisms and surface-dependent thin film nucleation and growth
- Surface passivation for controlled nucleation and growth
- Patterned deposition resists, including organic monolayers or polymers
- Chemical activation for nucleation enhancement
- Selectivity in thin film etching, including atomic layer etching (ALE)
- Precursor selection for area-selective deposition
- Processes and mechanisms for area-selective deposition using atomic layer deposition (ALD), molecular layer deposition (MLD), chemical vapor deposition (CVD), physical vapor deposition (PVD), and other thin film deposition techniques
- Metrology for area-selective deposition
- · Applications for area-selective deposition in electronics manufacturing
- Applications for area-selective processing in catalysis, energy generation and storage, and other emerging areas
- Surface characterization techniques for defects formation and mitigation

Programs

- · April 2: Tutorial of ASD (Profs. Greg Parsons, Sean Barry, Adrie Mackus)
- April 3rd 4th: ASD Workshop (11 invited speakers)
- April 5th: Special Session of ALD for Semiconductors (8 Invited speakers)

Key Dates

- Abstract Submission: Jan 16 Feb 6
- Pre-registration: Feb 13 Mar 3
- Author Acceptance Notifications: Feb 20

Sponsors























